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# **Question Paper Code: 42224**

M.E. DEGREE EXAMINATION, MAY 2015.

Second Semester

# **Communication Systems**

## 14PCM204 – MICROWAVE INTEGRATED CIRCUITS

(Regulation 2014)

Duration: Three hours

Maximum: 100 Marks

Answer ALL Questions.

PART A -  $(5 \times 1 = 5 \text{ Marks})$ 

- 1. A MIC, which consists of combination of two or more integrated circuit types is called as
  - (a) Monolithic IC (b) Hetero junction design
    - (c) Hybrid technology (d) Large scale integration
- 2. One important disadvantage of thick film technology is
  - (a) Reliability and Cost (b) Pattern definition
  - (c) Precision resistors (d) Temperature range
- 3. The advantage of Electron Beam Technology over photolithography is
  - (a) Low loss (b) Higher degree of resolution
  - (c) Higher spread (d) Low control
- 4. The mode of electromagnetic wave propagation in coplanar circuits is
  - (a) TE (b) TM (c) Quasi TEM (d) TEM
- 5. A Voltage controlled oscillator typically uses a
  - (a) Varactor diode (b) IMPATT diode
  - (c) Gunn diode (d) Zener diode

# PART - B (5 x 3 = 15 Marks)

6. List the advantage of MIC's compared to traditional circuits.

- 7. What are methods of testing in MMIC fabrication?
- 8. Give the steps involved in ion implantation.
- 9. Give the applications of high frequency capacitors.
- 10. Mention the features required for a LNA.

PART - C (
$$5 \times 16 = 80$$
 Marks)

11. (a) Give the reasons for increase in MIC technology development and also describe the design approaches for the design of MICs. (16)

#### Or

- (b) (i) Describe the technologies for multichip module design. (10)
  - (ii) Discuss the advantages and application of MMIC technology. (6)
- 12. (a) Distinguish between thick and thin film technologies? Explain the process and materials used for generating thin films. (16)

#### Or

- (b) Explain the methods of encapsulation and mounting of devices. (16)
- 13. (a) List the steps involved in MIC fabrication. Explain in detail the stages involved in epitaxial growth? (16)

#### Or

- (b) Explain the processes, applications and merits of electron beam technology. (16)
- 14. (a) Discuss the techniques for the design of capacitors and spiral inductors in MIC. (16)

#### Or

- (b) Describe how characteristic impedance, guide wavelength and effective dielectric constant are defined and expressed for microstrip lines. Explain the principle of multi layer microstrip lines. (16)
- 15. (a) Describe the construction and use of stability circles in microwave amplifier design and give the conditions for unconditional stability. (16)

### Or

(b) Discuss the conditions for oscillation of a microwave oscillator and the various feedback configurations for oscillator design. (16)